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(71) Applicant (for all designated States except US): **DOW GLOBAL TECHNOLOGIES INC.** [US/US]; Washington Street, 1790 Building, Midland, MI 48674 (US).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **GABELNICK, Aaron, M.** [US/US]; 111 S. Quarry Street, C8, Ithaca, NY 14850 (US). **LAMBERT, Christina, A.** [US/US]; 249 West Miller Road, Midland, MI 48642 (US). **WARAKOMSKI, John, M.** [US/US]; 2701 Mt. Vernon Drive, Midland, MI 48642 (US). **AERTS, Ludo, M.** [BE/BE]; Rechtsstraat 111, B-9160 Eksaarde (BE).

(74) Agent: **CHRISTY, M., Robert**; The Dow Chemical Company, Intellectual Property, P.O. Box 1967, Midland, MI 48641-1967 (US).

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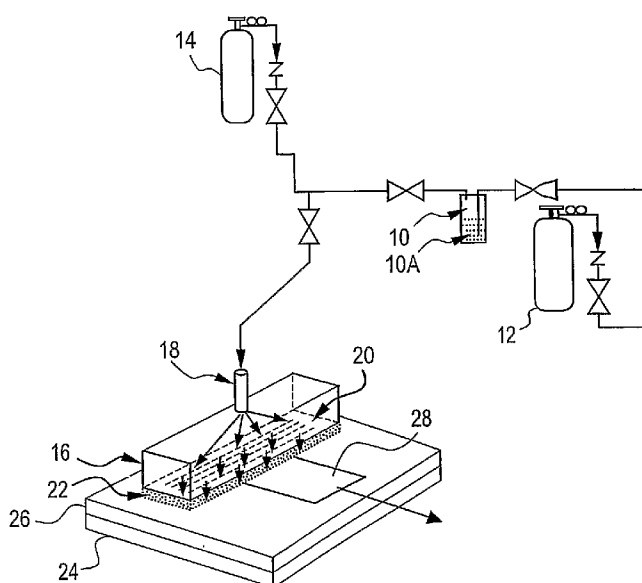
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(54) Title: ABRASION RESISTANT COATINGS BY PLASMA ENHANCED CHEMICAL VAPOR DEPOSITION



(57) Abstract: A process for preparing a multiple layer coating on the surface of an organic polymeric substrate by means of atmospheric pressure glow discharge deposition, the steps of the process comprising depositing a layer (first layer) of a plasma polymerized, optically clear, organosilicon compound and thereafter in a second step depositing a substantially uniform layer (second layer) of a polymeric siloxane or silicon oxide compound onto the exposed surface of said first layer, wherein the multiple layer coating has a thickness of at least 2.0 μm and an abrasion resistance demonstrating a change of 20 delta haze units or less after 500 Tabor cycles, measured according to ASTM D1044, CS10F wheels, 500 g weight.

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